

REMARKS

Claims 1 through 30 were presented for examination in the present application. Claims 14 through 21 have been withdrawn. Thus, claims 1 through 13 and 22 through 30 are presented for consideration upon entry of the instant amendment.

Claims 1 through 13 and 22 through 30 were rejected under 35 U.S.C. 112, first and second paragraphs. Independent claims 1 and 30 have been amended so as to nullify the rejections. In addition, because claims 2 through 13 and 22 through 29 depend from independent claim 1, the rejections to these claims are also nullified. Reconsideration and withdrawal of the rejections to claims 1 through 13 and 22 through 30 are respectfully requested.

Claims 1 through 11, 22, 23, 29, and 30 were rejected under 35 U.S.C. 102(e) as being anticipated by U.S. Patent No. 6,518,168 ("Clem"). Claim 12 was rejected under 35 U.S.C. 103(a) as being unpatentable over Clem, and further in view of U.S. Patent No. 5,688,642 ("Chrissey"). Claim 13 was rejected under 35 U.S.C. 103(a) as being unpatentable over Clem, and further in view of U.S. Patent No. 5,059,258 ("Wefers"). Claim 24 was rejected under 35 U.S.C. 103(a) as being unpatentable over Clem, and further in view of U.S. Patent No. 5,871,579 ("Liang"). Claims 25, 26, and 28 were rejected under 35 U.S.C. 103(a) as being unpatentable over Clem, and further in view of U.S. Patent No. 6,423,465 ("Hawker"). Claim 27 was rejected under 35 U.S.C. 103(a) as being unpatentable over Clem, and further in view of U.S. Patent No. 5,115,336 ("Schildkraut").

Independent claim 1 now recites "such that the patterned thin film is formed only on a surface of the substrate not coated with the self-assembled monolayer so that there is not a need for further post-deposition processing (emphasis added)".

Clem discloses that "A blocking agent such as a SAM is applied to surfaces serve to control nucleation and adhesion of overlayers of material from a precursor source, such as a CVD environment or a fluid precursor such as a sol-gel. Material from

such precursor sources adheres loosely and poorly to the blocking agent, or is formed thereon with poor structural characteristics, and can be removed from the blocking agent easily by thermal and/or mechanical agitation (emphasis added)". See, col. 5, line 62 – col. 6, line 3.

Clem further discloses that "A sol-gel precursor then is applied to the surface of the substrate by, for example, dip coating or spin-casting. After heat treatment amorphous oxide 19 forms at regions 22 and adheres well to the substrate, but above regions 20 oxide is poorly adhered and easily removed by thermal and/or mechanical agitation, resulting in the substrate 18 including oxide 19 patterned at portions 22 of the substrate surface, that is, deposited on the substrate surface in a pattern complementary to the SAM pattern (FIG. 1d) (emphasis added)". See, col. 6, lines 25 – 35.

Thus, in contrast to claim 1 which recites that there is not a need for further post-deposition processing, Clem clearly discloses the necessity for post-deposition processing including, for example, the application of thermal and mechanical agitation. As such, Clem fails to disclose or suggest the elements of claim 1. In addition, Applicants respectfully submit that none of the cited references, either alone or in combination, discloses or suggests the elements of claim 1. Claim 1 is in condition for allowance. Claims 2 through 13 and 22 through 29 depend from independent claim 1 are in condition for allowance for at least the reasons given above for claim 1. Reconsideration and withdrawal of the rejections to claims 1 through 13 and 22 through 29 are respectfully requested.

In addition, because claim 1 has been indicated as being generic, and because withdrawn claims 14 through 21 depend from independent claim 1, Applicants respectfully request rejoinder and allowance of claims 14 through 21.

Claims 30 now recites "so that there is not a need for further post-deposition processing (emphasis added)".

As discussed previously, Clem, either alone or in combination with the cited art, fails to disclose or suggest no need for further post-deposition procession. For at least this reason, claim 30 is in condition for allowance. Reconsideration and withdrawal of the rejection to claim 30 are respectfully requested.

In view of the above, it is respectfully submitted that the present application is in condition for allowance. Such action is solicited.

If for any reason the Examiner feels that consultation with Applicants' attorney would be helpful in the advancement of the prosecution, the Examiner is invited to call the telephone number below.

Respectfully submitted,

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